



SHEET 1 OF 1

Form PTO 1449  
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PATENT AND TRADEMARK OFFICE

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## LIST OF REFERENCES CITED BY APPLICANT

APPLICANT

Yukio TANIGUCHI, et al.

FILING DATE

March 18, 2004

GROUP

## U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						
	AL						
	AM						
	AN						

## FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION	
					YES	NO
	AO					
	AP					
	AQ					
	AR					
	AS					
	AT					
	AU					

## OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)

RK	AV	Chang-Ho OH, et al., Japan Journal of Applied Physics, vol. 37, pages L492-L495, "A NOVEL PHASE-MODULATED EXCIMER-LASER CRYSTALLIZATION METHOD OF SILICON THIN FILMS", May 1, 1998
RK	AW	M. NAKATA, et al., The Japan Society of Applied Physics, vol. 40, part 1, no. 5, pages 3049-3054, "A NEW NUCLEATION-SITE-CONTROL EXCIMER-LASER-CRYSTALLIZATION METHOD", May 2001
RK	AX	M. MATSUMURA, IDW '02 AMD5-1, pages 263-266, "ADVANCED LASER-CRYSTALLIZATION TECHNOLOGIES OF SI FOR HIGH-PERFORMANCE TFTs", 2001
RK	AY	International Display Workshops, pages 1-6, "ADVANCED LASER-CRYSTALLIZATION TECHNOLOGIES OF SI FOR HIGH-PERFORMANCES TFTs" (with partial English translation) 2(2002)
RK	AZ	Journal of The Surface Science Society of Japan, vol. 21, no. 5, pages 278-287, "PREPARATION OF ULTRA-LARGE GRAIN SILICON THIN-FILMS BY EXCIMER-LASER", 2000 (with partial English translation)

☐ Additional References sheet(s) attached

Examiner /Robert Runemund/

Date Considered 07/21/2006

\*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.